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# Generation current temperature scaling

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This talk is a summary of the Technical Note:  
A.Chilingarov, “Generation current temperature scaling” of  
9.5.2011. It can be reached at

[https://rd50.web.cern.ch/rd50/doc/Internal/rd50\\_2011\\_001-I-T\\_scaling.pdf](https://rd50.web.cern.ch/rd50/doc/Internal/rd50_2011_001-I-T_scaling.pdf)

The Note relies heavily on the Review: M.A.Green,  
“Intrinsic concentration, effective densities of states, and  
effective mass in silicon”, Journal of Applied Physics, 67  
(1990) 2944.

The current per unit area generated inside the depleted bulk can be written as:

$$J(T) = qWn_i/\tau_g$$

where  $q$  is elementary charge,  $W$  – depleted thickness,  $n_i$  – intrinsic carrier concentration and  $\tau_g$  – generation lifetime.

Temperature dependence of  $n_i$  can be expressed as:

$$n_i \propto T^{3/2} \exp(-E_g/2kT)$$

where  $E_g$  is the band gap.

Assuming generation happening via a trap with density  $N_t$  and level  $E_t$  in the band gap the generation lifetime can be written as:

$$\tau_g = \tau_p \exp(\Delta_t/kT) + \tau_n \exp(-\Delta_t/kT)$$

where  $\Delta_t = E_t - E_i$  ( $E_i$  is intrinsic Fermi level) and  $\tau_{p(n)}$  is the trapping time for holes (electrons):

$$\tau_p = 1/N_t v_{thp} \sigma_p ; \tau_n = 1/N_t v_{thn} \sigma_n .$$

Here  $v_{thp(n)}$  is the thermal velocity and  $\sigma_{p(n)}$  - trapping cross-section for holes (electrons).

Assuming that  $N_t$  and cross-sections are independent of temperature and neglecting weak temperature dependence of the effective carrier masses the trapping times can be scaled with temperature as:

$$\tau_{p(n)} \propto T^{-1/2} .$$

If  $\tau_p \approx \tau_n$  the  $\tau_g$  dependence on  $\Delta_t/kT$  is close to  $\cosh(\Delta_t/kT)$ . Thus  $\tau_g$  is at minimum and the current generation is most effective when  $\Delta_t \approx 0$ . For  $|\Delta_t|/kT > 1.5$  the  $\cosh$  is reduced to  $\exp(|\Delta_t|/kT)$ . Therefore the current scaling with temperature is usually expressed as:

$$I(T) \propto T^2 \exp(-(E_g + 2\Delta)/2kT)$$

where  $\Delta$  is a parameter close to  $|\Delta_t|$ .

The temperature dependence of the current is clearly dominated by that of  $n_i$ . Thus it is crucial to know  $n_i(T)$  in detail. A vast literature exists about the intrinsic carrier concentration. Here we rely on the 1990 Review by M.A.Green and concentrate on the temperature interval of  $\pm 30^\circ\text{C}$  most relevant to the present usage of Si detectors in Particle Physics.

The Review gives 3 experimental fits of measured  $n_i(T)$  in the form:

$$n_i \propto T^m \exp(-E_a/kT)$$

where  $E_a$  is so called activation energy. In two cases  $m=3/2$  with  $E_a = 0.605$  and  $0.603$  eV. In one case  $m=2.365$  and  $E_a=0.580$  eV. Around  $T=273\text{K}$  this dependence may be replaced by that with  $m=3/2$  and equivalent  $E_a^{eq}=0.601$  eV with better than 1% accuracy in the temperature interval of  $\pm 30^\circ\text{C}$ .

Combining all 3 experimental values one gets

$$E_a = 0.603 \pm 0.002 \text{ eV}$$

where uncertainty covers all available experimental data.

Thus the experimental value of the effective band gap for  $n_i(T)$  is:

$$E_{ef} = 2E_a = 1.206 \pm 0.004 \text{ eV.}$$

It looks inconsistent with the actual band gap,  $E_g$ , quoted by M.A.Green as 1.124 eV at 300K and 1.137 eV at 250K.

Note however that temperature independent  $E_{ef}$  should incorporate also the temperature dependence of  $E_g$ .

Most easily this is done if  $E_g(T)$  can in some temperature interval be expressed in a linear form:  $E_g = E_0 - \alpha T$ , where  $E_0$  is the extrapolation of  $E_g$  to  $T=0$ . Then:

$$A \exp(-E_g/2kT) = A \exp(-E_0/2kT + \alpha/2k) = A' \exp(-E_0/2kT).$$

M.A.Green gives for  $E_g(T)$  the linear equation valid within 1meV accuracy in the interval 250 – 415 K where

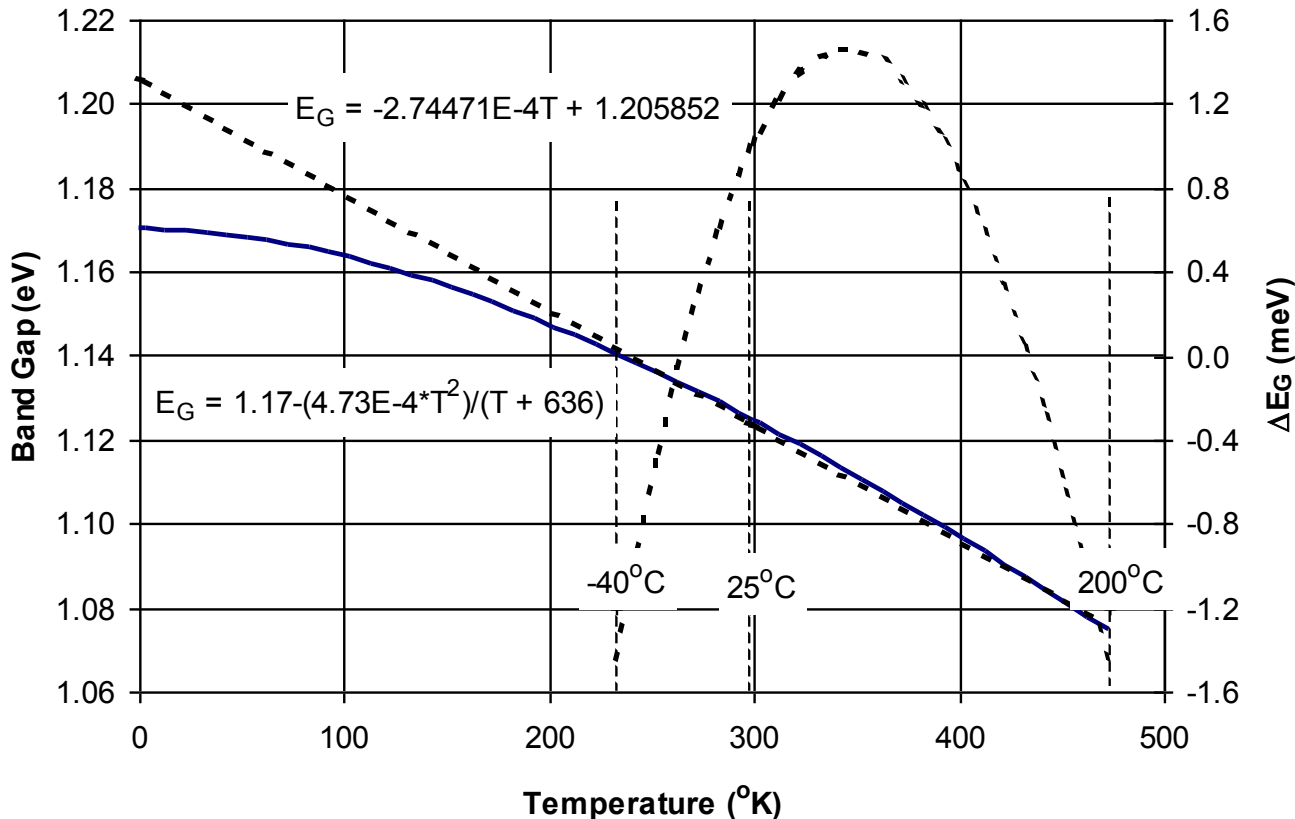
$$E_0 = 1.206 \text{ eV}$$

in perfect agreement with the experimental fits.



Thus the replacement of the temperature dependent band gap,  $E_g(T)$ , by a constant effective energy,  $E_{ef}$ , requires using not the actual  $E_g$  value at a typical temperature or its average value in the used temperature interval but the intercept at T=0,  $E_0$ , in the linear parameterisation of  $E_g$  at these temperatures. This is the property of the function  $\exp(-E_g(T) / kT)$ .

# Silicon Band Gap



This plot is taken from the 2002 talk “Band Gap Regulator Analysis” by J.B.Biard, Honeywell. (Many thanks to Graham Beck, QMUL for picking up this talk!)

From  $-40^\circ$  to  $+200^\circ\text{C}$  the  $E_g(T)$  can be expressed within 1.5meV accuracy by a linear equation with  $E_0 = 1.206\text{eV}$ .

For non-irradiated silicon it is usually assumed that generation proceeds via traps close to the mid gap i.e.  $\Delta=0$ . The current is then parameterised as  $T^2 \exp(-E/2kT)$  with  $E=E_g(T)$  or  $E_0$ .

The information on  $I(T)$  for irradiated sensors is quite limited. The survey made in 1994 [A.Chilingarov, H.Feick et al., NIM A360 (1995) 432] resulted in:

$$E_{ef} = 1.24 \pm 0.06 \text{ eV,}$$

which agrees with  $E_0=1.21$  eV obtained above but has a significant uncertainty. The ATLAS SCT recommends  $E_{ef}=1.21$  eV basing on irradiations by 24 GeV protons up to  $\sim 3 \cdot 10^{14}$  p/cm<sup>2</sup>.

Thus until proven otherwise the same temperature dependence with  $E_{ef} = 1.21$  eV may be used for both irradiated and non-irradiated silicon sensors.

# Conclusion

Within the range of  $\pm 30^\circ\text{C}$  the temperature dependence of the generation current can be described by the following parameterisation:

$$I(T) \propto T^2 \exp(-1.21\text{eV}/2kT)$$

both for non-irradiated and irradiated sensors. The difference between the effective and actual energy gaps is due to using constant  $E_{ef}$  instead of temperature dependent  $E_g(T)$ .

# Acknowledgement

The author is grateful to Graham Beck, QMUL, UK for helpful and illuminating discussions.

## Appendix

Known to the author publications with  $I(T)$  results in irradiated Si sensors.

1. T.Ohsugi et al., NIM A265 (1988) 105.
2. M.Nakamura et al., NIM A270 (1988) 42.
3. K.Gill et al., NIM A322 (1992) 177.
4. E.Barberis et al., NIM A326 (1993) 373.
5. H.Feick, PhD Thesis, DESY F35D-97-08, 1997.
6. L.Andricek et al., NIM A436(1999)262.

If you are aware of other publications on this topic please e-mail the reference to [a.chilingarov@lancaster.ac.uk](mailto:a.chilingarov@lancaster.ac.uk).

**Many thanks in advance! Alex**